

Resource Summary Report

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Oxford: PlasmaPro 100 ALE Plasma Technology

RRID:SCR_020372

Type: Tool

Proper Citation

Oxford: PlasmaPro 100 ALE Plasma Technology (RRID:SCR_020372)

Resource Information

URL: <https://plasma.oxinst.com/products/ale/plasmapro-100-ale>

Proper Citation: Oxford: PlasmaPro 100 ALE Plasma Technology (RRID:SCR_020372)

Description: PlasmaPro 100 ALE delivers precise process control to create and manipulate thinner layers through specialised hardware including precise control of gas dose, repeatability of low power RF delivery, and switching enabled by fast PLC.

Resource Type: instrument resource

Keywords: Oxford, Plasma Technology, Instrument, Resource equipment, Equipment, USEdit,

Availability: Commercially available

Resource Name: Oxford: PlasmaPro 100 ALE Plasma Technology

Resource ID: SCR_020372

Alternate IDs: Model_Number_100_ALE

Record Creation Time: 20220129T080350+0000

Record Last Update: 20260912T195935+0000

Ratings and Alerts

No rating or validation information has been found for Oxford: PlasmaPro 100 ALE Plasma Technology.

No alerts have been found for Oxford: PlasmaPro 100 ALE Plasma Technology.

Data and Source Information

Source: [SciCrunch Registry](#)

Usage and Citation Metrics

We have not found any literature mentions for this resource.